

Panel: Resist Performance, EUV Source Workshop

# **Nikon's perspective on the present status of resist performance and its effect on EUV source requirements**

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# Contribution of resist sensitivity to wafer throughput

$T_{exp}$ : Time required for expose a wafer

$$T_{exp} = R * A / P_w$$

$R$ : resist sensitivity,  $P_w$ : power at the wafer,  $A$ : area of the wafer

$$P_w = P_s * t_{opt}$$

$P_s$ : source power,  $t_{opt}$ : optical transmissivity (IFP → wafer)

$$\therefore T_{exp} = R * A / ( P_s * t_{opt} )$$

- The improvement of resist sensitivity, the improvement of source power and the improvement of optical transmissivity are completely equivalent.

***How shall we share the efforts?***

**Can the target wafer throughput be reduced?**